

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	4	Choi-Jinhan.in.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/17 10:29
L2	1	Lee-Jae-Gyoo.in.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/17 10:29
L3	4	1 or 2	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/17 10:34
L5	2638	216/67.ccls.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/17 10:34
L6	201	216/68.ccls.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/17 10:34
L7	298	216/71.ccls.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/17 10:34
L8	242	216/72.ccls.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/17 10:35
L9	1158	216/79.ccls.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/17 10:41
L10	737	5 and "CF.sub.4"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/17 10:41
L11	445	10 and RF	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/17 10:41
L12	302	9 and "CF.Sub.4"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/17 10:41
L13	171	12 and RF	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/17 10:41
S1	6175	(tetra\$1fluoride or "CF.sub.4" or "C.sub.4 F.sub.8" or "C.sub.4 F.sub.6") with ("CHF.sub.3" or "CH.Sub.2 F.sub.2" or "CH.Sub.3 F")	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 14:21
S2	5766	S1 and @ay<="2003"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/11 13:41
S3	2957	S1 same (oxide or di\$1oxide or SiO or "SiO.sub.2")	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 15:10

S4	2783	S3 and @ay<="2003"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/11 13:42
S5	2293	S4 and (resist or photo\$1resist or photo\$1sensitive)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/11 14:50
S6	255	S5 and (inductive or ICP induction)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/11 13:43
S7	607	(tetra\$1fluoride or "CF.sub.4") with "CH.sub.2 F.sub.2"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/11 14:50
S8	248	S7 same (oxide or di\$1oxide or SiO or "SiO.sub.2" or TEOS)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/11 14:50
S9	243	S8 and @ay<="2003"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/11 14:50
S10	192	S9 and (resist or photo\$1resist or photo\$1sensitive)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/11 17:11
S11	131955	IPS	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/11 17:11
S12	350	IPS with plasma	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/11 17:12
S13	113	IPS! with plasma	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/11 17:12
S14	1	"6247792".pn.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 14:07
S15	6175	(tetra\$1fluoride or "CF.sub.4" or "C.sub.4 F.sub.8" or "C.sub.4 F. sub.6") with ("CHF.sub.3" or "CH. sub.2 F.sub.2" or "CH.sub.3 F")	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 15:10
S16	635	S15 and ((inductive or inductively or antenna) same (power or watt))	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 14:45
S17	644	S15 and ((inductive or inductively or antenna or IPS!) same (power or watt))	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 14:22
S18	597	S17 and @ay<="2003"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 14:23
S19	481	S18 and (resist or photo\$1resist or photo\$1sensitive)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 14:23

S20	467	S19 and (oxide or di\$1oxide or SiO or "SiO.sub.2")	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 14:24
S21	441	S19 and ((oxide or di\$1oxide or SiO or "SiO.sub.2") same (etch or etching))	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 14:24
S22	344	S20 and (selectivity or (etch\$3 adj ratio))	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 14:25
S23	207	S20 and ((selectivity or (etch\$3 adj ratio)) with (resist or photo\$1resist or photo\$1sensitive))	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 14:25
S24	106	S15 and ((inductive or inductively or antenna) with (watt))	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 14:45
S25	101	S24 and @ay<="2003"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 15:06
S26	3715	S15 and density	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 15:07
S27	628	S26 and ((resist or photo\$1resist or photo\$1sensitive) with (selectivity or (etch\$3 adj rate)))	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 15:10
S28	523	S27 and (density near5 (plasma or high))	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 15:08
S29	486	S28 and @ay<="2003"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 15:08
S30	6	S29 and "HeO.sub.2"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 15:09
S31	2957	S15 same (oxide or di\$1oxide or SiO or "SiO.sub.2")	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 16:25
S32	1866	S26 and S31	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 15:10
S33	291	S32 and ((resist or photo\$1resist or photo\$1sensitive) with (selectivity or (etch\$3 adj rate)))	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 15:10
S34	273	S33 and @ay<="2003"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 16:23
S35	1	"5501893".pn.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 16:23

S36	20	S31 and "HeO.sub.2"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 17:02
S37	45	S15 and "HeO.sub.2"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 17:02
S38	25	S37 not S36	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/12 17:02
S39	2198	(selective or selectivity) with (oxide or SiO or "SiO.sub.2") with (resist or photo\$1resist or photo\$1sensitive)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/16 18:00
S40	119	S39 same "CF.sub.4"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/16 18:00